

Form PTO-1449

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)

3526.2US (97-1136.02/US)

Application Number

09/585,682

Applicant K t al.

Filing Date Jun 1, 2000

Group Art Unit 2815

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
C.C.	4,529,476	07/1985	Kawamoto et al.	156	643	
C.C.	6,018,184	01/2000	Becker	257	368	
C.C.	6,066,555	05/2000	Nulty et al.	438	634	
C.C.	6,117,791	09/2000	Ko et al.	438	723	
C.C.	6,277,720 B1	08/2001	Doshi et al.	438	586	
C.C.	6,303,496 B1	10/2001	Yu	438	668	

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
C.C.	61251138	08/1986	JP	—	—	X	
C.C.	0721205 A2	07/1996	EPO	—	—		
C.C.	WO 98/49719	11/1998	PCT				

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

C.C.		Wolf, S., et al., Silicon Processing for the VLSI Era, Vol. 1, Process Technology, Lattice Press, 1986, pp. 520-523.
C.C.		Williams, K., BSAC Etch Rates for Micromachining and IC Processing, U.C. Berkeley Microfabrication Lab., Berkeley Sensor & Actuator Center, http://www-bsac.eecs.berkeley.edu/db/etchrates.html .
C.C.		Williams, K., VLSI Etchants, Chapter 1.5, Rev. 11/97, http://microlab.berkeley.edu/labmanual/chap1/1.5.html .

EXAMINER

DATE CONSIDERED

11/4/03

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.